ISPlasma2019/IC-PLANTS2019

11th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials
12th International Conference on Plasma-Nano Technology & Science

March 17-21, 2019
Nagoya Institute of Technology
Nagoya, Japan

Organizing Committee

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Sponsored by : The Japan Society of Applied Physics

Co-Sponsored by : Nagoya University, Nagoya Institute of Technology, Meijo University, Chubu University

http://www.isplasma.jp/

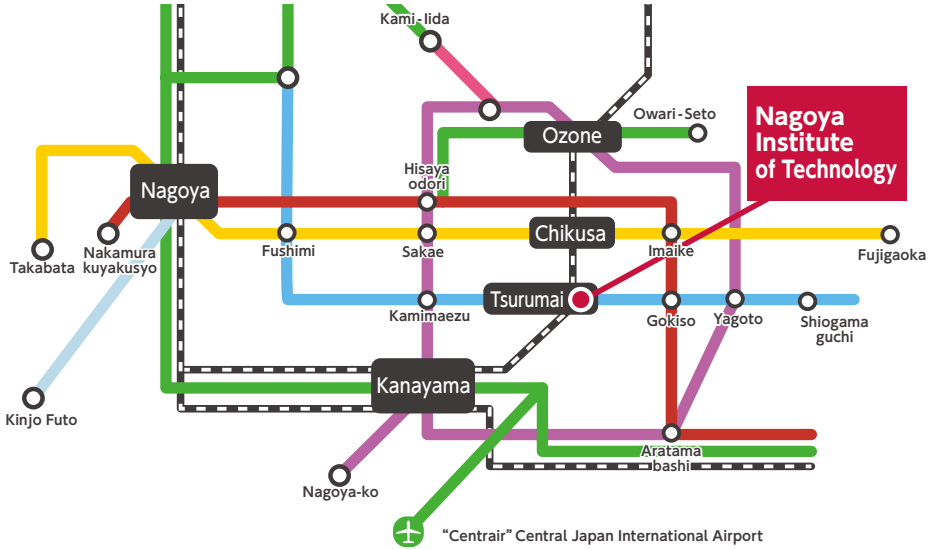
Registration

Advanced online registration is required.

		General	Student
Registration Fee :	Early Registration (Until Jan 31, 2019)	JPY 45,000	JPY 15,000
	On-site Registration	JPY 50,000	JPY 20,000
Tutorial Fee :	Participant in Main Symposium	JPY 1,000	JPY 1,000
	Tutorial Registration Only	JPY 10,000	JPY 5,000
Banquet Fee (on March 19, 2019)		JPY 6,000	JPY 3,000

* Refunds cannot be made at any reason.

Access



Meitetsu Airport Line Central Japan International Airport Station
26 min. by rapid train
Meitetsu Line Kanayama Station
Kanayama Station
2 min. by Train JR Chuo Line
Tsurumai Station
7 min. on foot
Nagoya Station
7 min. by Train JR Chuo Line
Nagoya Institute of Technology

Contact

Secretariat : Inter Group Corp.
E-mail : isplasma2019@intergroup.co.jp Website : http://www.isplasma.jp/

ISPlasma/IC-PLANTS is a specialized international symposium that brings together about 500 world-leading scientists and engineers in Nagoya, Japan to discuss latest researches in the fields of advanced plasma science, its applications for processing and manufacturing of nitrides and nanomaterials, as well as new systems for technology transfers. This symposium will address issues such as global warming, resources and energy problems to which advanced plasma science and its application technologies can greatly contribute. In this symposium biosensing technologies will be also highlighted, because of their increasing importance in healthcare, agri-food and environmental areas. We hope that this symposium will provide an ideal venue for the exchange of new ideas and information, and also support the initiation or further development of international collaborations among those who work in these multidisciplinary fields.

Related Fields

Plasma Science & Technologies

- Plasma Source
- Modeling & Simulation
- Thin Film Deposition Process
- Flexible Electronics
- Advanced Plasma Diagnostics
- Plasma in Liquid
- Etching Process
- Plasma for Nano & Green Technologies

Nitride Semiconductors

- Crystal Growth of GaN & Related Materials
- Characterization
- Optical & Optoelectronic Devices
- MBE Growth & Nitrogen Source
- Device Processing
- Electron & Power Devices

Nanomaterials

- Nanodots & Nanoparticles
- 2D Nanomaterials
- Composites & Functionally Graded Materials
- Applications for Energy
- Nanotubes, Nanowires & Nanorods
- Porous Materials & Membranes
- Surface Modification & Functionalization
- Nanomedicine & Sensing

Bio Applications

- Plasma Biology & Medicine
- Plasma Agriculture
- Biomaterials
- Biomarkers
- Bioimaging
- Bio-Devices, μTAS, Lab on a Chip
- Bioensors
- Device Fabrication Technologies

Abstract Submission

Online abstract submission (one-page English) is available from **http://www.isplasma.jp/**

Submission Deadline：Monday, October 1, 2018 JST

Special Issue

Selected papers will be published in a special issue of a scientific journal.

Tutorial

Tutorial for Plasma Science, Nitride Semiconductors, Nanomaterials, and Bio Applications will be held on Sun, March 17, 13:00

PROGRAM

Plenary Speaker

M. Kawai (Institute for Molecular Science, JAPAN)

Keynote Speakers

K. J. Chen (Hong Kong University of Science and Technology, HONG KONG)
G. S. Hwang (University of Texas, U.S.A.)
D. Mariotti (Ulster University, U.K.)
H. Metelmann (University Medicine Greifswald, GERMANY)

Prof. Riccardo d'Agostino Memorial Session Speakers

P. Favia (University of Bari, ITALY)
T. C. Wei (Chung Yuan Christian University, TAIWAN)

Invited Speakers

D. Biswas (Nagoya Institute of Technology, JAPAN)
S. F. Chichibu (Tohoku University, JAPAN)
E. H. Choi (Kwangwoon University, KOREA)
T. Doi (Doi Laboratory Inc., Kyushu University, Saitama University, JAPAN)
G. Fridman (Drexel University, U.S.A.)
J. Ikeda (Osaka University, JAPAN)
M. Jo (RIKEN, JAPAN)
A. Kaminska (Polish Academy of Science, POLAND)
S. Kamiyama (Meijo University, JAPAN)
T. Kato (Tohoku University, JAPAN)
M. Keider (The George Washington University, U.S.A.)
A. Komuro (Tohoku University, JAPAN)
J. Kuzmik (Slovak Academy of Sciences, SLOVAKIA)
H. Lee (KAIST, KOREA)
Y. Liu (San Yat-sen University, CHINA)
E. Martines (Consorzio RFX, ITALY)
G. D. Masi (Consorzio RFX, ITALY)
T. Moriya (Tokyo Electron Limited., JAPAN)
Y. Nakamura (Osaka University, JAPAN)
T. Narita (Toyota Central R&D Labs., Inc., JAPAN)
T. Otsuji (Tohoku University, JAPAN)
Y. Pei (San Yat-sen University, CHINA)
J. Pouvesle (CNRS, FRANCE)
M. Sakuraba (Tohoku University, JAPAN)
S. Sanguinetti (Universita' degli Studi di Milano-Bicocca, ITALY)
Y. Sano (Osaka University, JAPAN)
T. Sasaki (AIST, JAPAN)
T. Shibata (DOWA Electronics Materials Co., Ltd., JAPAN)
M. Shigeta (Osaka University, JAPAN)
R. Short (Lancaster University, U.K.)
Y. H. Song (Korea Institute of Machinery and Materials, KOREA)
Q. Sun (Suzhou Institute of Nano-tech and Nano-bionics (SINANO), CHINA)
M. R. Vasquez (University of the Philippines, PHILIPPINES)
J. S. Wu (National Chiao Tung University, TAIWAN)
Y. Yamanishi (Kyushu University, JAPAN)

Tutorial Speakers

U. Cvelbar (Jožef Stefan Institute, SLOVENIA)
T. Hashizume (Hokkaido University, JAPAN)
T. Watanabe (Kyushu University, JAPAN)